



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Ted A. Loxley
Serial No. : 09/490,162
Filed : January 22, 2000
For : PROCESS AND APPARATUS FOR
CLEANING SILICON WAFERS
Examiner : Viktor Simkovic - Technology Center 2800
Docket No. : 104

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Amendment After Allowance
Under 37 CFR 1.312

Sir:

Please amend the above-identified application by deleting the last paragraph of page 56 and replacing it with the following paragraph:

-- In the practice of the present invention electro-purge cleaning with low-voltage wafer charges, such as 2 to 8 volts, can be effective with the dilute RCA and ultra-dilute RCA (SC-1 and SC-2 cleans with or without the assistance of megasonic energy (which can be damaging to delicate nanoscale micro-circuits)). --